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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.	
09/921,560	08/06/2001	Koji Matsukuma	102392.01	7818	
25944 * 7	590 07/30/2003			.03.	
OLIFF & BERRIDGE, PLC			EXAMINER		
P.O. BOX 19928 ALEXANDRIA, VA 22320			COLEMAN, WILLIAM D		
			ART UNIT	PAPER NUMBER	
•		•	2823		

Please find below and/or attached an Office communication concerning this application or proceeding.

<u> </u>	·			pl.		
9		Application No.	Applicant(s)			
		09/921,560	MATSUKUMA, KO	JI .		
	Office Action Summary	Examiner	Art Unit	•		
· 		W. David Coleman	2823			
Period fo	The MAILING DATE of this communication app or Reply	ears on the cover sh	et with the correspond nc add	iress		
A SH THE I - Exter after - If the - If NO - Failu - Any r earne	ORTENED STATUTORY PERIOD FOR REPLY MAILING DATE OF THIS COMMUNICATION. Insions of time may be available under the provisions of 37 CFR 1.13 SIX (6) MONTHS from the mailing date of this communication. Period for reply specified above is less than thirty (30) days, a reply or period for reply is specified above, the maximum statutory period we to reply within the set or extended period for reply will, by statute, reply received by the Office later than three months after the mailing and patent term adjustment. See 37 CFR 1.704(b).	36(a). In no event, however, m within the statutory minimum of vill apply and will expire SIX (6) cause the application to becom	ay a reply be timely filed of thirty (30) days will be considered timely. MONTHS from the mailing date of this connected the connected that the co	mmunication.		
Status	December to communication(s) filed as 40.	l 0000				
1)[Responsive to communication(s) filed on 19 J	,				
2a)☐		is action is non-final.		*		
3)	Since this application is in condition for allowa closed in accordance with the practice under			ements is		
· _	on of Claims					
	Claim(s) <u>27-32 and 38-43</u> is/are pending in the		•	•		
	4a) Of the above claim(s) is/are withdrav	vn from consideration		• •		
	Claim(s) is/are allowed.					
	Claim(s) <u>27-32 and 38-43</u> is/are rejected.			•		
7)	Claim(s) is/are objected to.					
	Claim(s) are subject to restriction and/or on Papers	r election requirement	*			
	The specification is objected to by the Examiner	•				
	The drawing(s) filed on is/are: a) accep		hy the Examiner			
.0,	Applicant may not request that any objection to the			X-		
11)□	The proposed drawing correction filed on		•	er.		
,	If approved, corrected drawings are required in rep					
12)	The oath or declaration is objected to by the Exa	aminer.				
Priority u	ınder 35 U.S.C. §§ 119 and 120	•				
13)🖾	Acknowledgment is made of a claim for foreign	priority under 35 U.S	.C. § 119(a)-(d) or (f).			
	☑ All b)☐ Some * c)☐ None of:					
	1. Certified copies of the priority documents	s have been received.	•			
	2. Certified copies of the priority documents have been received in Application No. <u>09/219,707</u> .					
* S	3. Copies of the certified copies of the prior application from the International Bur See the attached detailed Office action for a list	reau (PCT Rule 17.2(a	a)).	Stage		
	acknowledgment is made of a claim for domestic	·	•	application)		
a) The translation of the foreign language pro	visional application ha	as been received.	application,		
	Acknowledgment is made of a claim for domesti	c priority under 35 U.S	5.C. 99 120 and/or 121.			
Attachmen		4) [] Intern	view Summary (DTO 412) Dance Note	e)		
2) Notic	e of References Cited (PTO-892) e of Draftsperson's Patent Drawing Review (PTO-948) nation Disclosure Statement(s) (PTO-1449) Paper No(s)	5) 🔲 Notic	view Summary (PTO-413) Paper No(s se of Informal Patent Application (PTC r:			
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DETAILED ACTION

Continued Examination Under 37 CFR 1.114

1. A request for continued examination under 37 CFR 1.114, including the fee set forth in 37 CFR 1.17(e), was filed in this application after final rejection. Since this application is eligible for continued examination under 37 CFR 1.114, and the fee set forth in 37 CFR 1.17(e) has been timely paid, the finality of the previous Office action has been withdrawn pursuant to 37 CFR 1.114. Applicant's submission filed on June 19, 2003 has been entered.

Claim Rejections - 35 USC § 102

2. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

- (b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.
- 3. Claims 27-30 and 38-42 are rejected under 35 U.S.C. 102(b) as being anticipated by Livesay, U.S. Patent 5,468,595.
- Livesay discloses a etching mask as claimed for claim 27. See FIGS. 1-13, where Livesay teaches an etching mask for selectively etching a workpiece, wherein the etching mask is made of a metal 69 and has a cross-sectional shape comprising a rectangular first region that determines a pattern width of the workpiece, and a second region that contacts the first region and intercept application of etching beams to a sidewall of the first region during etching.
- 5. Pertaining to claim 28, <u>Livesay</u> teaches an etching mask for selectively etching a workpiece, wherein the etching mask is made of a metal and has a cross-sectional shape comprising a rectangular first region that determines a pattern width of the workpiece, and a

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second region that intercepts application of etching beams to a sidewall of the first region during etching, wherein the etching mask has a T-shaped cross section.

- 6. Pertaining to claim 29, <u>Livesay</u> discloses the teaching mask according to claim 28, comprising a cross section including a vertical bar having an end that contacts with a surface of the workpiece, and a lateral bar placed on another end of the vertical bar and having a width greater than a width of the vertical bar, wherein a pattern width of the workpiece is determined by the width of the vertical bar.
- 7. Pertaining to claim 30, <u>Livesay</u> discloses an etching mask for selectively etching a workpiece, wherein the etching mask is made of a metal and has a cross-sectional shape comprising a rectangular first region that determines a pattern width of the workpiece, and a second region that intercepts application of etching beams to a sidewall of the first region during etching, wherein the first region is a vertical bar having an end that contacts with a surface of the workpiece, and the second region is a lateral bar placed on another end of the vertical bar hand having a width greater than a width of the vertical bar, wherein a pattern width of the workpiece is determined by the width of the vertical bar.
- 8. Pertaining to claim 38, <u>Livesay</u> teaches an etching mask for selectively etching a workpiece, wherein the etching mask is made of a metal and has a cross-sectional shape comprising a rectangular first region that determines a pattern width of the workpiece and a second region that contacts the first region and intercepts application of etching beans to a sidewall of the first region during etching, wherein the first region has a first height and a first width and the second region has a second width, and wherein the second width is greater than the first width and first height is grater than the second height.

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- 9. Pertaining to claim 39, <u>Livesay</u> teaches an etching mask for selectively etching a workpiece, wherein the etching mask is made of a metal and has cross-sectional shape comprising a rectangular first region that determines a pattern width of the workpiece and a second region that intercepts application of etching beams to a sidewall of the first region during etching, wherein the etching mask has a T-shape cross-section, wherein the first region has a first height and a first width and a second region has a second height and a second width, and wherein the second width is greater than the firs width and first height is greater than the second height.
- 10. Pertaining to claim 40, <u>Livesay</u> teaches the etching mask of claim 38 wherein the second region continuously contacts the first region along the first width of the first region.
- 11. Pertaining to claim 41, <u>Livesay</u> teaches the etching mask of claim 39 wherein the second region continuously contacts the first region along the first width of the first region.
- 12. Pertaining to claim 42, <u>Livesay</u> teaches wherein the vertical bar continuously contacts the lateral bar along the entire width of the vertical bar.

Claim Rejections - 35 USC § 103

- 13. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
 - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 14. Claims 31 and 32 are rejected under 35 U.S.C. 103(a) as being unpatentable over Livesay, U.S. Patent 5,468,595 as applied to claims 27, 28, 29 and 30 above and further in view of Hirano, et al., U.S. Patent 5,652,157.

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15. Pertaining to claims 31, 32 and 43, <u>Livesay</u> teaches a semiconductor process substantially as claimed, wherein the etching mask according to claims 28 and 27 is a metal. However, <u>Livesay</u> fails to disclose that the metal is selected from the group consisting of Au (gold). Hirano teaches wherein the metal consist of Au (gold). In view of Hirano, it would have been obvious to one of ordinary skill in the art to incorporate gold as a metal mask in the Livesay semiconductor process because it provides a process for forming dummy gates (see title).

Conclusion

- 16. Any inquiry concerning this communication or earlier communications from the examiner should be directed to W. David Coleman whose telephone number is 703-305-0004. The examiner can normally be reached on 9:00 AM-5:00 PM.
- 17. If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Olik Chaudhuri can be reached on 703-306-2794. The fax phone numbers for the organization where this application or proceeding is assigned are 703-308-7722 for regular communications and 703-308-7721 for After Final communications.
- 18. Any inquiry of a general nature or relating to the status of this application or proceeding should be directed to the receptionist whose telephone number is 703-308-0956.

W. David Coleman Primary Examiner Art Unit 2823

WDC July 21, 2003